

# **Ultraviolet photoelectron spectroscopy and electron stimulated desorption from CaF<sub>2</sub>**

Im Fachbereich Physik  
der Freien Universität Berlin  
eingereichte Dissertation von  
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Berlin, November 1998

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# Contents

<b>1. Introduction</b>	<b>6</b>
<b>2. The investigated material: Calcium fluoride</b>	<b>10</b>
2.1. Structure of the CaF <sub>2</sub> crystal	10
2.2. Defects and surface defects in CaF <sub>2</sub>	13
2.3. Defect aggregation: Metal colloids	17
2.4. Stopping power and penetration depth of low energy electrons in CaF <sub>2</sub>	20
2.5. Mean free path in insulators	22
<b>3. Photoemission</b>	<b>24</b>
3.1. Angular resolved photoemission	24
3.2. Dipole selection rules	28
<b>4. Experimental setup</b>	<b>30</b>
4.1. UHV system	30
4.2. Ultraviolet photoelectron spectroscopy (UPS)	32
4.3. Optical spectroscopy	33
4.4. Electron stimulated desorption (ESD)	34
4.5. Preparation of thin epitaxial CaF <sub>2</sub> films on Si (111)	35
<b>5. Ultraviolet photoelectron spectroscopy from CaF<sub>2</sub></b>	<b>37</b>
5.1. Introduction	37
5.2. Basic features	38
5.2.1. Introduction	38
5.2.2. Photoemission from the UHV cleaved surface and energy reference	38
5.2.3. Phonon broadening of photoemission lines	45
5.2.4. Influence of electron-phonon interaction on photoelectron angular distribution	48
5.2.5. Photoconductivity during UV irradiation	52
5.2.6. Summary	55
5.3. Photoemission from differently prepared CaF <sub>2</sub> (111) surfaces	57
5.3.1. Introduction	57
5.3.2. Comparison of photoemission from UHV and air cleaved CaF <sub>2</sub> crystals	57
5.3.3. Photoemission from thin CaF <sub>2</sub> films evaporated on Si(111)	61

5.3.4	Gas dosage to CaF <sub>2</sub> surfaces	66
5.3.5.	Photoemission from polished surfaces	70
5.3.6	Summary	73
5.4.	Irradiation induced effects in CaF <sub>2</sub>	74
5.4.1	Introduction	74
5.4.2	Electron irradiation effects at high temperature	75
5.4.3	Electron irradiation effects at low temperature	80
5.4.4	Photon irradiation induced effects	82
5.4.5.	Photon induced surface reactions with oxygen	84
5.4.6.	Comparison of experimental results on oxidized CaF <sub>2</sub> surfaces to theoretical predictions	87
5.4.7	Summary	90
<b>6.</b>	<b>Optical transmission spectroscopy on CaF<sub>2</sub></b>	<b>92</b>
<b>7.</b>	<b>Electron stimulated desorption (ESD)</b>	<b>97</b>
7.1	Introduction	97
7.2.	Surface potential determination	98
7.2.1	Introduction	98
7.2.2	Charging during electron irradiation	98
7.2.3	Technique for surface potential determination	100
7.2.4	The influence of surface stoichiometry on the surface potential	102
7.2.5	Dependence of surface potential on primary energy and beam current	107
7.2.6	Summary and conclusions	108
7.3.	Kinetic energy of F <sup>+</sup> ions desorbing from CaF <sub>2</sub>	110
7.3.1	Introduction	110
7.3.2	Electron stimulated desorption from CaF <sub>2</sub> via the Knotek-Feibelman mechanism	110
7.3.3	Charge corrected F <sup>+</sup> kinetic energies	112
7.3.4	Influence of surface stoichiometry on desorption energies	119
7.3.5	Summary	120
7.4.	Field driven diffusion	121
7.4.1	Introduction	121
7.4.2	Electron irradiation induced field inside the crystal	122
7.4.3	Temporal evolution of ion yield of crystals and thin films	123

7.4.4 Summary	126
7.5. Desorption from epitaxial CaF <sub>2</sub> films	127
7.5.1 Desorption from thin epitaxial CaF <sub>2</sub> films	127
7.5.2 Summary	131
<b>8. Summary</b>	<b>132</b>
<b>9. Bibliography</b>	<b>135</b>

Parts of this work are published in:

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Ich versichere, die vorliegende Arbeit selbständig verfaßt und keine anderen als die angegebenen Hilfsmittel benutzt zu haben.

Berlin, im November 1998

## Danksagung

Zunächst gilt mein Dank allen Mitgliedern der Arbeitsgruppe Matthias für das immer gute Arbeitsklima. Die folgenden Personen haben zum Gelingen der Arbeit besonders beigetragen:

Ich danke:

Herrn Matthias für zahlreiche fruchtbare Diskussionen und Ideen sowie für sein stets vorhandenes Interesse an Photoemission und Desorption,

Michael Reichling für die ständige gute Zusammenarbeit, ausdauernde gute Laune und sorgfältiges Korrekturlesen,

Roland Bennewitz, der im Nachbarlabor  $\text{CaF}_2$  mit dem Rasterkraftmikroskop untersuchte.

Die Absorptionsspektren habe ich zusammen mit Nicolas Bouchaala gemessen. Svante Wellershoff brachte seine Computerkenntnisse ein. Die Berechnungen zur elektronischen Struktur von  $\text{CaF}_2$  stammen von Vladimir Puchin, mit dem zusammen ich auch einige Ideen zur Desorption entwickelt habe.

Peter West konnte sämtliche Computerprobleme lösen.

Ferner den siamesischen Desorbierern Elmar Stenzel & Stephan Gogoll ("SteGo") sowie Dietgart Mallwitz, V. Kempfer, R.T. Williams und meinem Zweitgutachter Herrn Rieder.